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(21)Application number: 04-290961 (71)Applicant: TOKYO OHKA KOGYO CO LTD

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(54) COATING LIQUID COMPOSITION FOR CHEMICALLY AMPLIFIED RESIST (57)Abstract:

PURPOSE: To prevent multiple interference in a resist film in lithographic processing by coating the chemically amplified resist film with the composition containing a water-soluble film-forming component and a proton generating substance to form a film on the surface.

CONSTITUTION: The water-soluble film-forming component can be embodied by a water-soluble polymer, such as hydroxypropylmethyl cellulose phthalate and a vinyl polymer like polyvinylpyrrolidone. Water-soluble polymers having no hydroxyl groups in the molecule, such as polyacrylate and polyvinylpyrrolidone, are preferable. As the proton generating substance, inorganic acid, such as hydrochloric acid and nitric acid, and organic acids, such as trifluoroacetic acid, are preferable. The water-soluble film-forming component and the proton generating substance are contained in an amount of 0.5-10weight%, and 0.01-1.0weight%, respectively.

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